

## **Amendments to the Claims**

1. (Original): A plasma enhanced chemical vapor deposition method of forming a titanium silicide comprising layer over a substrate using a reactive gas comprising  $\text{TiCl}_4$  and at least one silane, comprising:

providing a substrate within a plasma enhanced chemical vapor deposition chamber;

first feeding  $\text{TiCl}_4$  to the chamber without feeding any measurable silane to the chamber for a first period of time; and

after the first feeding for the first period of time, second feeding  $\text{TiCl}_4$  and at least one silane to the chamber for a second period of time effective to plasma enhance chemical vapor deposit a titanium silicide comprising layer on the substrate.

2. (Original): The method of claim 1 wherein the second feeding occurs at selected chamber deposition pressure and substrate temperature conditions, the first feeding also occurring at the selected second feeding chamber deposition pressure and substrate temperature conditions.

3. (Original): The method of claim 1 wherein the feeding of  $\text{TiCl}_4$  during the first and second feedings is at a substantially constant volumetric flow rate.

4. (Original): The method of claim 1 wherein the feeding of  $\text{TiCl}_4$  during the first and second feedings is at different volumetric flow rates.

5. (Original): The method of claim 1 wherein nothing other than  $\text{TiCl}_4$  is fed to the chamber during the first period of time.

6. (Original): The method of claim 1 wherein the first period of time is less than the second period of time.

7. (Original): The method of claim 1 wherein the first period of time is no greater than 5 seconds.

8. (Original): The method of claim 1 wherein the first period of time is no greater than 3 seconds.

9. (Original): The method of claim 1 wherein,  
the second feeding occurs at selected chamber deposition pressure and substrate temperature conditions, the first feeding also occurring at the selected second feeding chamber deposition pressure and substrate temperature conditions; and

the first period of time is less than the second period of time.

10. (Original): The method of claim 1 wherein the first feeding comprises plasma generation within the chamber.

11. (Original): The method of claim 1 wherein the first feeding does not comprise plasma generation within the chamber.

Claims 12-40 (Canceled).